

PTO/SB/08A (08-03)

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 5

| | |
|----------------------|---------------------|
| Application Number | 10/678,438 |
| Filing Date | 3 October 2003 |
| First Named Inventor | Vladimir V. MAKAROV |
| Art Unit | |
| Examiner Name | |

Attorney Docket Number 65.0395

U. S. PATENT DOCUMENTS

| Examiner Initials* | Cite No. ¹ | Document Number Number-Kind Code ² (if known) | Publication Date MM-DD-YYYY | Name of Patentee or Applicant of Cited Document | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear |
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| SA | | JP4173988 | 11-02-1990 | Nissin Electric | | ✓ |
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|--------------------|--------------|-----------------|---------|
| Examiner Signature | Shamim Ahmed | Date Considered | 6/22/05 |
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Sheet 2 of 5

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| Application Number | 10/678,438 |
| Filing Date | 3 October 2003 |
| First Named Inventor | Vladimir V. MAKAROV |
| Art Unit | |
| Examiner Name | |
| Attorney Docket Number | 65.0395 |

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

Examiner
Signature

Shamim Ahmed

Date
Considered

6/22/05

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| | | | | Art Unit | |
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| Sheet 3 | of 5 | Attorney Docket Number | 65.0395 | | |

| NON PATENT LITERATURE DOCUMENTS | | | | | |
|---------------------------------|-----------------------|---|--|--|--|
| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | | | |
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| Examiner Signature | Shamim Ahmed | Date Considered | 6/22/05 |
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| | | | | Attorney Docket Number | 65.0395 |

| NON PATENT LITERATURE DOCUMENTS | | | |
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| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | |
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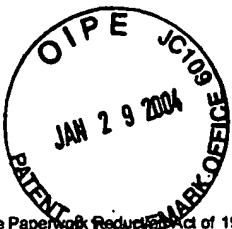
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First Named Inventor

Vladimir V. MAKAROV

Art Unit

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NON PATENT LITERATURE DOCUMENTS

| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
|--------------------|-----------------------|---|----------------|
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